

**ELECTRICAL AND MATERIAL CHARACTERIZATION OF 0.24  
MICRON CMOS DEVICE BY USING SIMULATION**

**BY :**

**NAZIRAH MOHAMAT KASIM**

**AHMAD PUAD ISMAIL**

**ROSFARIZA RADZALI**

**APRIL 2009**



Tarikh : 24 Disember 2007  
Surat Kami : 600-IRDC/ST.5/3/1365

Pn. Nazirah Binti Mohamat Kasim  
Ketua Projek  
UiTM Pulau Pinang  
Jalan Permatang Pauh  
13500 Permatang Pauh  
**PULAU PINANG**

En. Ahmad Puad Bin Ismail  
Ahli Projek  
UiTM Pulau Pinang  
Jalan Permatang Pauh  
13500 Permatang Pauh  
**PULAU PINANG**

Pn. Rosfariza Radzali  
Ahli Projek  
UiTM Pulau Pinang  
Jalan Permatang Pauh  
13500 Permatang Pauh  
**PULAU PINANG**

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**PROF. DR. AZNI ZAIN AHMED**  
Penolong Naib Canselor (Penyelidikan)

Tarikh: 20 April 2009  
No. Fail Projek: 600-IRDC/ST.5/3/1365

Penolong Naib Canselor (Penyelidikan)  
Institut Pengurusan Penyelidikan (RMI)  
Universiti Teknologi MARA  
40450 Shah Alam  
SELANGOR

Y. Bhg. Prof.,

**LAPORAN AKHIR PENYELIDIKAN "ELECTRICAL AND MATERIAL  
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Terima kasih.

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## ABSTRACT

This project is to simulate and analyze the electrical characteristics for 0.24 micron CMOS device using SILVACO TCAD. The objective of the project is basically to simulate the fabrication process and electrical characterization for 0.24 micron CMOS devices. Electrical characteristics were carried out by using Atlas simulator while, simulation of the process is carried out by using Athena process simulator to modify theoretical values and obtain more accurate process parameters. At the device simulation process, the electrical parameter was extracted to investigate the device characteristics. Several design analysis are performed to investigate the effectiveness of the advanced method in order to prevent the varying of threshold voltage. The electrical characteristics produces the graph of drain current versus drain voltage,  $I_D-V_D$  and drain current versus gate voltage,  $I_D-V_G$ . From  $I_D-V_G$  can be obtained the threshold voltage,  $V_T$  where  $V_T$  for NMOS transistor is lower than  $V_T$  for PMOS transistor which is 0.6695V and -0.9683 V respectively. The gate length,  $L_G$  obtained from the simulated for NMOS and PMOS are same which is 0.235 micron and it is nearest to the scale for the project can be obtained.